

**Influence of quantum confinement on the electronic structure of the transition metal sulfide  $TS_2$** 

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(Received 22 February 2011; revised manuscript received 27 April 2011; published 30 June 2011)

Bulk  $MoS_2$ , a prototypical layered transition-metal dichalcogenide, is an indirect band gap semiconductor. Reducing its slab thickness to a monolayer,  $MoS_2$  undergoes a transition to the direct band semiconductor. We support this experimental observation by first-principle calculations and show that quantum confinement in layered  $d$ -electron dichalcogenides results in tuning the electronic structure. We further studied the properties of related  $TS_2$  nanolayers ( $T = W, Nb, Re$ ) and show that the isotopological  $WS_2$  exhibits similar electronic properties, while  $NbS_2$  and  $ReS_2$  remain metallic independent of the slab thickness.

DOI: [10.1103/PhysRevB.83.245213](https://doi.org/10.1103/PhysRevB.83.245213)

PACS number(s): 71.20.Nr, 73.22.-f

**I. INTRODUCTION**

Layered transition-metal dichalcogenides (LTMDCs) of  $TX_2$  type ( $T = Mo, W, Nb, Re, Ti, Ta, \text{etc.}, X = S, Se, Te, \text{etc.}$ ) have been studied extensively on the experimentally and theoretically for the last 40 years.<sup>1-17</sup> Molybdenum disulfide ( $MoS_2$ ) is a prototypical LTMDC, which is composed of two-dimensional S–Mo–S sheets stacked on the top of one another, as shown in Fig. 1. Each sheet is trilayered with a Mo atom in the middle that is covalently bonded to six S atoms located in the top and bottom layers. The bonding between the adjacent S–Mo–S sheets is much weaker and they are held together by weak interlayer bonds leading to the quasi-2D character of  $MoS_2$ .

Due to the weak forces between the sheets and the anisotropic character of LTMDCs, shearing takes place more easily even under high pressure, leading to lubricant applications.<sup>3,18</sup> Other applications, such as catalysis, optoelectronics, and photovoltaics, have been proposed and investigated.<sup>1,4,5,19-21</sup> A single layer of  $MoS_2$  was recently used to realize a field-effect transistor with  $HfO_2$  as a gate insulator.<sup>22</sup> The transistor exhibits a room-temperature current on/off ratio exceeding  $1 \times 10^8$  and mobility comparable to the mobility of thin silicon films or graphene nanoribbons. Two-dimensional sheets of layered materials can be produced nowadays by, e.g., liquid exfoliation, what was successfully performed in the case of transition-metal dichalcogenides by Coleman *et al.*<sup>23</sup>

The electronic structure of various bulk TMDCs and a monolayer of  $MoS_2$  have been previously studied throughout *ab initio* calculations using the plane waves approach or local basis functions.<sup>7,9,10,12,14</sup>  $MoS_2$  is an indirect band gap material in its bulk form, which recently was shown to become a direct band gap semiconductor when thinned to a monolayer.<sup>12,16,24</sup> Therefore, few-layer- $MoS_2$  materials can have their band gaps tuned and their values shift from the bulk value by at least 500 meV due to quantum size effects.

In this paper, we have studied slab-thickness-dependent electronic properties of  $TS_2$  type, where  $T = Mo, W, Re, \text{and } Nb$ . The first-principle calculations were performed using localised Gaussian basis functions and compared to the available experimental data and plane wave calculations. The results show that the indirect-direct band gap transition also holds for  $WS_2$ . The band structures of  $ReS_2$  and  $NbS_2$  reveal

metallic character and therefore, no such transition appears. It can be expected that the size-dependent phenomenon of band gap transition will occur also for other dichalcogenides, such as  $MoSe_2, WSe_2, MoTe_2, \text{or } WTe_2$ . This study is in progress and will be the subject of our next communication.

**II. METHODS**

In this work, we have studied LTMDCs of  $TS_2$  type, where  $T = Mo, W, Re, \text{and } Nb$ . All structures have hexagonal symmetry and belong to the  $P6_3/mmc$  space group.  $ReS_2$  is a triclinic system but for the purposes of a direct comparison, we have used hexagonal symmetry. The monolayers and polylayers were cut out from the fully optimized bulk structures as (0 0 1) surfaces. Different numbers of layers were considered in this study: mono-, bi-, and quadrilayers, as well as, six- and eight-layered structures.

First-principle calculations were performed on the basis of density functional theory (DFT) as implemented in the CRYSTAL09 code.<sup>25</sup> The exchange and correlation terms were described using general gradient approximation (GGA) in the scheme of PBE (Perdew-Burke-Ernzerhof)<sup>26</sup> and PBE

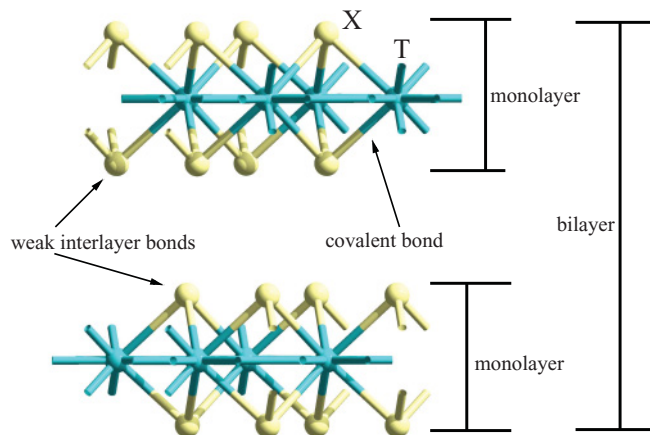


FIG. 1. (Color online) The atomic structure of layered transition-metal dichalcogenides of  $TX_2$  type ( $T$ , transition metal;  $X$ , chalcogenide). Different sheets of  $TX_2$  are composed of three atomic layers  $X-T-X$ , where  $T$  and  $X$  are covalently bonded. Sheets are held together by weak interlayer bonds.

TABLE I. Calculated and experimental lattice parameters of hexagonal transition-metal dichalcogenides in the form of  $TX_2$  ( $T = \text{Mo, W, Nb, Re}$ ;  $X = \text{S, Se}$ ). Results obtained at the DFT/PBE level. In parentheses, data obtained at the DFT/PBE0 level are given.

Structure	Theory		Expt. (Refs. 1, 2, 6)	
	$a$	$c$	$a$	$c$
MoS <sub>2</sub>	3.173 (3.143)	12.696 (12.583)	3.160	12.295
WS <sub>2</sub>	3.164 (3.139)	12.473 (12.380)	3.154	12.362
NbS <sub>2</sub>	3.332 (3.313)	12.106 (12.074)	3.310	11.890
ReS <sub>2</sub>	3.300 (3.275)	12.724 (12.148)	...	...

hybrid (PBE0) functionals.<sup>27</sup> The following Gaussian basis sets were used: Mo\_SC\_HAYWSC-311(d31)G\_cora\_1997 (for Mo atoms), W\_cora\_1996 (for W atoms), Nb\_SC\_HAYWSC-31(d31)G\_dallolio\_1996 (for Nb atoms), Re\_cora\_1991 (for Re atoms), and S.86-311G\*\_lichanot\_1993 (for S atoms). The chalcogenide atoms were calculated using full-electron basis sets, while for the heavy elements, the effective core potential (ECP) approach was employed. The large-core ECP has been chosen, what leaves only the valence electrons to be explicitly described on the metal sites:  $4d$  and  $5sp$  for Mo and Nb,  $5d$  and  $6sp$  for W and Re.

In CRYSTAL09 code, the 3D and 2D structures are treated as crystal and slab structures, respectively, therefore, in the case of layers there is no need to introduce vacuum.

Optimization of initial experimental structures was performed using analytical energy gradients with respect to atomic coordinates and unit cell parameters within a quasi-Newton scheme combined with the BFGS (Broyden-Fletcher-Goldfarb-Shanno) scheme for Hessian updation. The optimized lattice parameters for all the studied materials are given in Table I.

The shrinking factor (commensurate grid of k-points in reciprocal space at which the KS matrix is diagonalized) for bulk and layered structures was set to 8, what results in the corresponding number of 50 and 30 k-points in the irreducible Brillouin zone, respectively. The mesh of k-points was obtained according to the scheme proposed by Monkhorst and Pack.<sup>28</sup> Band structures were calculated along the high symmetry points using the path  $\Gamma$ - $M$ - $K$ - $\Gamma$ .

### III. RESULTS AND DISCUSSION

We have studied electronic properties of  $TS_2$  layered structures with respect to the slab thickness of the systems. Bulk structures as well as mono- and polylayers were considered. DFT is widely used in the field of solid-state physics and it gives excellent structural parameters (see Table I) and charge distribution; however, typically it does not represent the electronic structure correctly. Therefore, we have introduced two different exchange-correlation functionals (PBE and PBE0) to address this problem specifically.

Figures 2 and 3 show band structures of MoS<sub>2</sub> and WS<sub>2</sub>, respectively, calculated using PBE functional and going from bulk to a monolayer. (For band structures results using PBE0 functional see supplemental material).<sup>29</sup>

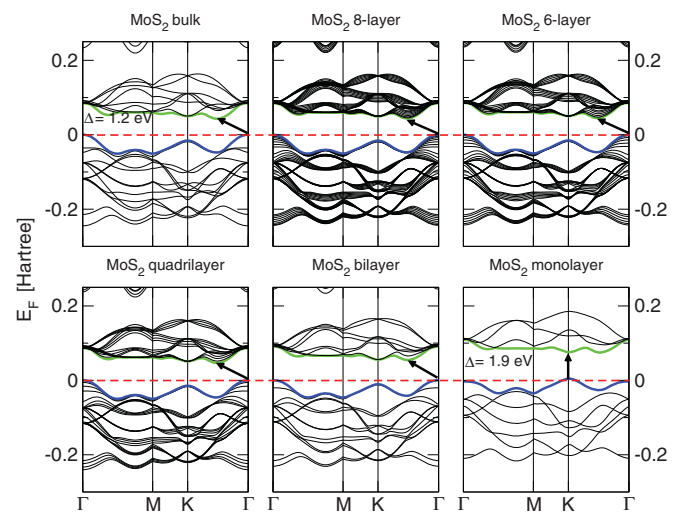


FIG. 2. (Color online) Band structures of bulk MoS<sub>2</sub>, its monolayer, as well as, polylayers calculated at the DFT/PBE level. The horizontal dashed lines indicate the Fermi level. The arrows indicate the fundamental band gap (direct or indirect) for a given system. The top of valence band (blue/dark gray) and bottom of conduction band (green/light gray) are highlighted.

The results show that bulk MoS<sub>2</sub> and WS<sub>2</sub> are indirect-gap semiconductors. The fundamental band gap originates from transition from the top of valence band situated at  $\Gamma$  to the bottom of conduction band halfway between  $\Gamma$  and  $K$  high symmetry points. The optical direct band gap is situated at  $K$  point. As the number of layers decreases, the fundamental indirect band gap increases and becomes so high in the monolayer that the material changes into a 2D direct band gap semiconductor. At the same time, the optical direct gap (at the  $K$  point) stays almost unchanged (independent of the slab thickness) and close to the value of the optical direct band gap

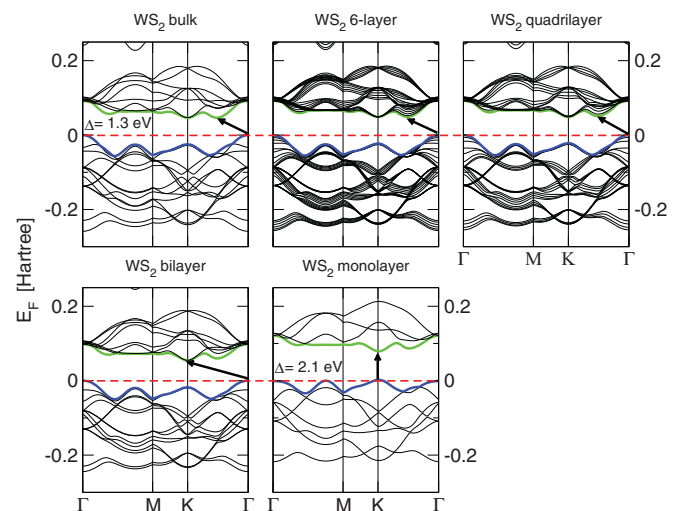


FIG. 3. (Color online) Band structures of bulk WS<sub>2</sub>, its monolayer, as well as, polylayers calculated at the DFT/PBE level. The horizontal dashed lines indicate the Fermi level. The arrows indicate the fundamental band gap (direct or indirect) for a given system. The top of valence band (blue/dark gray) and bottom of conduction band (green/light gray) are highlighted.

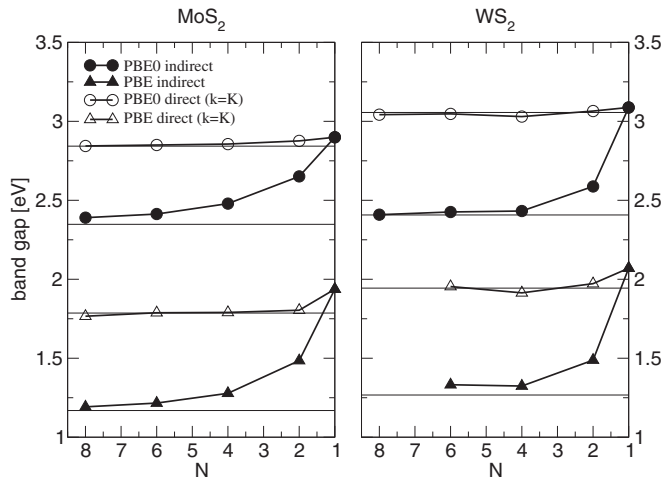


FIG. 4. Calculated direct and indirect band gap values of  $\text{MoS}_2$  and  $\text{WS}_2$   $N$ -layer slabs. The horizontal solid lines indicate the band gaps of bulk structures.

(at the  $K$  point) of a bulk system. These results are visualized better in Fig. 4, where the band gap of  $\text{MoS}_2$  and  $\text{WS}_2$  are plotted against the number of layers.

There is a significant difference in the band gap values calculated using PBE and PBE0 functionals. Comparing the results with the available experimental data, one can see that the PBE functional performs better. The fundamental indirect band gap of bulk  $\text{MoS}_2$  is 1.23 eV (Ref. 4) and our value of 1.2 eV agrees perfectly at the PBE level, while it is overestimated by around 1 eV using PBE0 hybrid functional. Similarly, the band gap of  $\text{WS}_2$ , with experimental value of 1.35 eV,<sup>4</sup> is 1.3 eV at the PBE level and 2.4 eV using PBE0. The experimental direct band gaps (at the  $K$  points) of  $\text{MoS}_2$  and  $\text{WS}_2$  are 1.74 and 1.79 eV, respectively.<sup>4</sup> Our DFT/PBE calculations give values of 1.8 and 1.9 eV for  $\text{MoS}_2$  and  $\text{WS}_2$ , respectively. Again, the PBE0 results are overestimated by around 1 eV.

Li *et al.*,<sup>14</sup> using GGA/PBE functional and the plane wave approach, obtained band gap of 0.79 eV for the bulk  $\text{MoS}_2$ . For the same system, Matte *et al.*<sup>16</sup> have obtained 1.1 and 1.70 eV for the indirect and direct band gap, respectively, using GGA/PBE and DZP basis set. Using Perdew-Wang exchange-correlation functional and self-consistent pseudopotential, Arora *et al.*<sup>11</sup> have obtained the indirect band gap of 1.32 eV for the  $\text{WS}_2$  bulk.

Decreasing the number of layers causes progressive shift in the indirect gap up to 1.9 and 2.1 eV for  $\text{MoS}_2$  and  $\text{WS}_2$ , respectively. The change in the indirect gap energy is significantly larger than that of the direct gap (at the  $K$  point), which increased by around 0.1 eV. Similar results were found by Mak *et al.*<sup>13</sup> for  $\text{MoS}_2$ .

The band gaps of bulk structures are in the range of near infrared. Reducing the number of monolayers in the material to just a few layers causes the blueshift in absorption features and shifts the band gap to the range of the visible light. These materials can be, therefore, interesting in optoelectronics.

These unusual electronic structures of  $\text{MoS}_2$  and  $\text{WS}_2$ , and the resulting optical properties come from the  $d$ -electron orbitals that dominate the valence and conduction bands (see

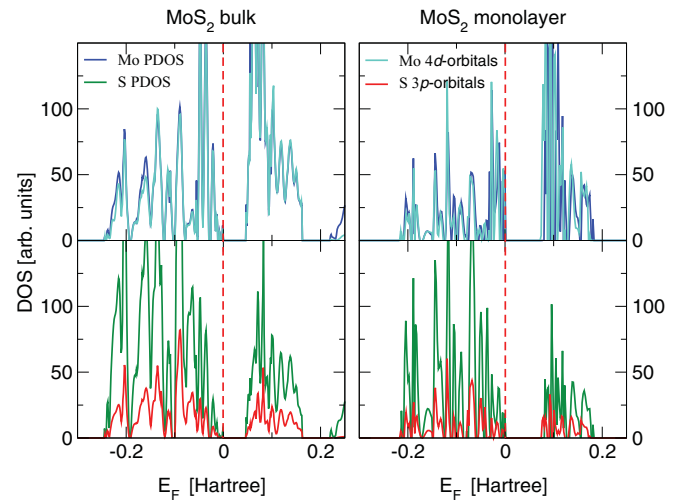


FIG. 5. (Color online) Partial density of states of bulk  $\text{MoS}_2$  and its monolayer calculated as the DFT/PBE. The projections of Mo and S atoms are given together with the contributions from 4d and 3p orbitals of Mo and S, respectively. The vertical dashed lines indicate the Fermi level.

Fig. 5 for  $\text{MoS}_2$ ). The projected density of states (PDOS) of  $\text{TS}_2$  shows that  $p$ -states of sulfur atoms hybridize with the  $d$ -states of the transition metal atoms at the top of valence band and the bottom of conduction band. The core states are dominated by the  $s$ -orbitals of the chalcogenide atom.

We have also studied the role of quantum confinement in niobium and rhenium disulfides and if their band gaps can be tuned by changing the slab thickness of the material. The electronic band structures of  $\text{NbS}_2$  and  $\text{ReS}_2$  (see Fig. 6) are different from those discussed above, especially close to the Fermi level. Although all the studied sulfides are isotopological, the  $\text{NbS}_2$  and  $\text{ReS}_2$  materials have metallic character independent of the number of layers.

The metallic character of  $\text{NbS}_2$  comes from the fact that the  $4d_{z^2}$  orbital is half-filled and results in a band that crosses the Fermi level in several points in the Brillouin zone. The band

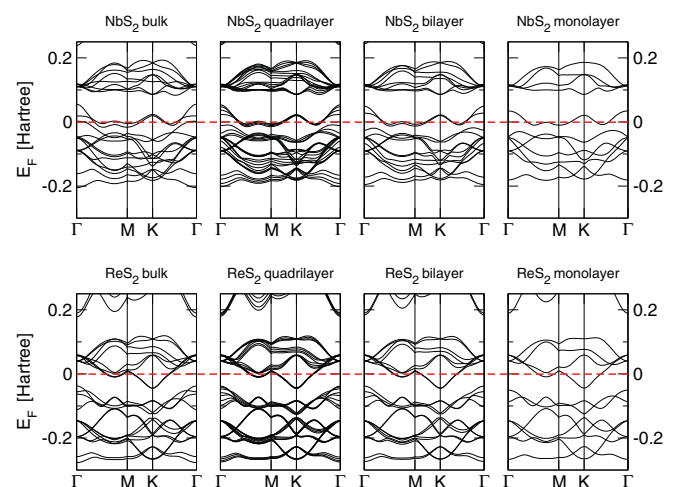


FIG. 6. (Color online) Band structures of bulk  $\text{NbS}_2$  and  $\text{ReS}_2$ , their monolayer, as well as polylayers calculated at the DFT/PBE level. The horizontal dashed lines indicate the Fermi level.

at the Fermi level is derived primarily from these  $4d$ -orbitals and becomes separated from all other states in a monolayer.

The structure of  $\text{ReS}_2$  studied here is of the same symmetry as all the other LTMDCs, even though the experimentally obtained material is triclinic.  $\text{ReS}_2$  has one electron per metal atom more than  $\text{MoS}_2$  and has a metallic character similar to  $\text{NbS}_2$ . The band that crosses the Fermi level comes from the  $5d$ -orbitals of Re atoms. Unlike  $\text{NbS}_2$ , this band is not separated even in the monolayer and the electronic structure in the vicinity of the Fermi level is determined by short-range interactions in the sulfur  $3p$  and rhenium  $5d$  band complex.

For both,  $\text{NbS}_2$  and  $\text{ReS}_2$ , the electronic structure of a bulk can be resemble by a single layer of these compounds.

#### IV. CONCLUSIONS

We have studied layered transition-metal dichalcogenides in form of  $TS_2$  by means of GGA-DFT (PBE) and a

hybrid functional (PBE0). The former was found to match experimental results for the band gap of the bulk phases within less than 0.1 eV, while PBE0 overestimates the band gap by 1 eV, but gives otherwise very similar band structures. Our DFT, at the PBE level, supports the recent findings of Splendiani *et al.*<sup>12</sup> for  $\text{MoS}_2$ : the material changes its electronic properties from an indirect semiconductor in the bulk phase to a direct semiconductor in the monolayer, an interesting phenomenon with potential application for optical devices. We show that  $\text{WS}_2$  has very similar properties and can be considered as alternative material. On the other hand, both  $\text{ReS}_2$  and  $\text{NbS}_2$  systems have metallic character independent of the number of layers.

The LTMDCs, if mixed together, have interesting and promising technological potential, especially for nanoelectronics and catalysis. Therefore, we are presently working on the properties of doped structures of transition-metal dichalcogenides.

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<sup>29</sup>See Supplemental Material at <http://link.aps.org/supplemental/10.1103/PhysRevB.83.245213> for the electronic structures of  $TS_2$  bulk, mono- and poly-layers calculated using PBE0 functional.